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(21) International Application Number: PCT/EP98/07754 (22) International Filing Date: 1 December 1998 (01.12.98) (30) Priority Data: 08/991,034 15 December 1997 (15.12.97) US (71) Applicant: CLARIANT INTERNATIONAL, LTD. [CH/CH]; Rothausstrasse 61, CH-4132 Muttenz 1 (CH). (72) Inventors: RAHMAN, M., Dalil; 62 Concord Ridge Road, Flemington, NJ 08822 (US). COOK, Michelle, M.; Apart- ment 5H, 776 Eves Drive, Somerville, NJ 08876 (US). LU, Ping-Hung; 473 Steeple Chase Lane, Bridgewater, NJ 08807 (US). (74) Agent: HÜTTER, Klaus; Clariant GmbH, Patente, Marken und Lizenzen, Building K 801, Room 2027, D-65926 Frankfurt am Main (DE).		(81) Designated States: CN, JP, KR, SG, European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE). Published <i>With international search report. Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>
(54) Title: FRACTIONATED NOVOLAK RESIN AND PHOTORESIST COMPOSITION THEREFROM (57) Abstract The present invention provides a method for producing a film forming, fractionated novolak resin having consistent molecular weight and superior performance in photoresist composition, by isolating such a novolak resin fraction. A method is also provided for producing photoresist composition from such a fractionated novolak resin and for producing semiconductor devices using such a photoresist composition.		